

## KISM 2025 BUSAN

Re:Innovation of Semiconductor Manufacturing for AI Ecosystem

[TuA1] Nanoscale	Thin Film	<b>Deposition I</b>
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Session Date November 11 (Tue.), 2025

**Session Time** 13:00-14:40

Session Room Room A (Capri Room, 2F)

[TuA1-1] [Invited] 13:00-13:30

Selective Atomic Layer Deposition in Advancing Semiconductor Manufacturing

Rong Chen (Huazhong Univ. of Science and Tech., China)

[TuA1-2] [Invited] 13:30-14:00

Development of a Selective-Area ALD Process for Buried Word Line in DRAM

Jongho Lee (SK hynix Inc., Korea)

[TuA1-3] [Invited] 14:00-14:20

Novel Organic Molecular Inhibitors for Improved Step Coverage in High-Temperature ALD Dielectrics

Seung Hyun Lee, Deok Hyun Kim, Kok Chew Tan, Sung Gi Kim, Jung Hun Lim, Young-Soo Park, and Jaesun Jung (Soulbrain Co., Ltd., Korea)

[TuA1-4] 14:20-14:40

Enhancing Oxide/Nitride Selectivity in Area-Selective ALD via Pyridine-Catalyzed Inhibition Jieun Oh, Woohyuk Kim, and Woo-Hee Kim (Hanyang Univ., Korea)